L Number	Hits	Search Text	DB	Time stamp
11	3309	high adj k	USPAT;	2004/09/25
**	3309	ingiradj k	US-PGPUB	20:06
12	1682	high?k	USPAT;	2004/09/25
12	1002	Ingili K	US-PGPUB	20:06
13	28618	gate adj insulat\$3	USPAT;	2004/09/25
	20010	gate day modulation	US-PGPUB	20:07
14	10063	gate adj dielectric	USPAT;	2004/09/25
- '	10000	gate day dispositio	US-PGPUB	20:07
15	137421	silicon adj \$2oxide	USPAT;	2004/09/25
			US-PGPUB	20:08
16	134924	"SiO.sub.2"	USPAT;	2004/09/25
			US-PGPUB	20:08
17	124649	anneal\$3	USPAT;	2004/09/25
			US-PGPUB	20:08
18	1429975	heat\$3	USPAT;	2004/09/25
			US-PGPUB	20:09
19	304	(((high adj k) or high?k) same ((gate adj insulat\$3)	USPAT;	2004/09/25
		or (gate adj dielectric))) and (((silicon adj \$20xide)	US-PGPUB	20:12
		or "SiO.sub.2") same (anneal\$3 or heat\$3))		
20	68	(((high adj k) or high?k) same ((gate adj insulat\$3)	USPAT;	2004/09/25
		or (gate adj dielectric))) same (((silicon adj \$20xide)	US-PGPUB	22:33
		or "SiO.sub.2") same (anneal\$3 or heat\$3))		
21	659481	interfac\$3	USPAT;	2004/09/25
			US-PGPUB	22:41
22	798	((high adj k) or high?k) with ((gate adj insulat\$3) or	USPAT;	2004/09/25
		(gate adj dielectric))	US-PGPUB	22:42
23	606969	oxide	USPAT;	2004/09/25
			US-PGPUB	22:42
24	21	(((high adj k) or high?k) with ((gate adj insulat\$3)	USPAT;	2004/09/25
1		or (gate adj dielectric))) same ((silicon adj \$20xide)	US-PGPUB	22:56
		or "SiO.sub.2" or oxide) same (anneal\$3 or heat\$3)		
	_	same interfac\$3		
25	7	("4495219"   "5436410"   "5486488"   "5508221"	USPAT	2004/09/25
0.5		"5622888"   "6150209"   "6246105").PN.		22:46
26	476654	oxygen or "O.sub.2"	USPAT;	2004/09/25
0.7	10115		US-PGPUB	22:57
27	12115	nitrous adj oxide or "N.sub.20"	USPAT;	2004/09/25
28	170565	ammania an "NIII amb 2"	US-PGPUB	22:57
20	170565	ammonia or "NH.sub.3"	USPAT;	2004/09/25
29	595149	hydrogen or "H.sub.2"	US-PGPUB USPAT;	22:59
127	555179	injurogen or misuo.2	USPAT; US-PGPUB	2004/09/25 23:00
30	6	(((high adj k) or high?k) with ((gate adj insulat\$3)	USPAT;	2004/09/25
		or (gate adj dielectric))) same (anneal\$3 or heat\$3)	US-PGPUB	23:03
ĺ		same ((oxygen or "O.sub.2") or (nitrous adj oxide or	00-1 01 05	20.00
		"N.sub.20")) same ((ammonia or "NH.sub.3") or		
		(hydrogen or "H.sub.2"))		
31	7		USPAT;	2004/09/25
		heat\$3)) same interfac\$3 same ((oxygen or	US-PGPUB	23:11
1		"O.sub.2") or (nitrous adj oxide or "N.sub.20") or		
1		(ammonia or "NH.sub.3") or (hydrogen or		
		"H.sub.2"))		
32	30	(((high adj k) or high?k) near3 (anneal\$3 or	USPAT;	2004/09/25
		heat\$3)) same interfac\$3	US-PGPUB	23:28
33	12392	tantalum adj \$5oxide or "Ta.sub.2O.sub.5"	USPAT;	2004/09/25
			US-PGPUB	23:31
34	81288	titanium adj oxide or "TiO.sub.2"	USPAT;	2004/09/25
			US-PGPUB	23:31
35	36673	zirconium adj oxide or "ZrO.sub.2"	USPAT;	2004/09/25
	L		US-PGPUB	23:31

36	5340	Hafnium adj oxide or "HfO.sub.2"	USPAT;	2004/09/25
			US-PGPUB	23:32
37	7939554	nitrogen adj oxide or NO	USPAT;	2004/09/25
			US-PGPUB	23:32
38	1232428	water or "H.sub.20"	USPAT;	2004/09/25
			US-PGPUB	23:32
39	5	(((high adj k) or high?k) near3 ((gate adj insulat\$3)	USPAT;	2004/09/25
		or (gate adj dielectric))) and ((tantalum adj \$50xide	US-PGPUB	23:37
		or "Ta.sub.2O.sub.5") or (titanium adj oxide or		
		"TiO.sub.2") or (zirconium adj oxide or "ZrO.sub.2")		
		or (Hafnium adj oxide or "HfO.sub.2")) same		
		(anneal\$3 or heat\$3) same (ammonia or		
		"NH.sub.3") same ((oxygen or "O.sub.2") or (nitrous		
		adj oxide or "N.sub.2O") or (nitrogen adj oxide or		
		NO) or (water or "H.sub.2O"))		
40	108	(((high adj k) or high?k) near3 ((gate adj insulat\$3)	USPAT;	2004/09/26
		or (gate adj dielectric))) and (((tantalum adj \$50xide	US-PGPUB	01:07
		or "Ta.sub.2O.sub.5") or (titanium adj oxide or		
		"TiO.sub.2") or (zirconium adj oxide or "ZrO.sub.2")		İ
		or (Hafnium adj oxide or "HfO.sub.2")) same		÷ .
		(anneal\$3 or heat\$3))		
41	13635	high adj dielectric adj constant	USPAT;	2004/09/26
			US-PGPUB	01:08
43	103	((high adj dielectric adj constant) near3 ((gate adj	USPAT;	2004/09/26
		insulat\$3) or (gate adj dielectric))) and ((anneal\$3	US-PGPUB	01:11
		or heat\$3) same interfac\$3)		
42	10	((high adj dielectric adj constant) near3 ((gate adj	USPAT;	2004/09/26
		insulat\$3) or (gate adj dielectric))) same (anneal\$3	US-PGPUB	01:11
		or heat\$3) same interfac\$3		